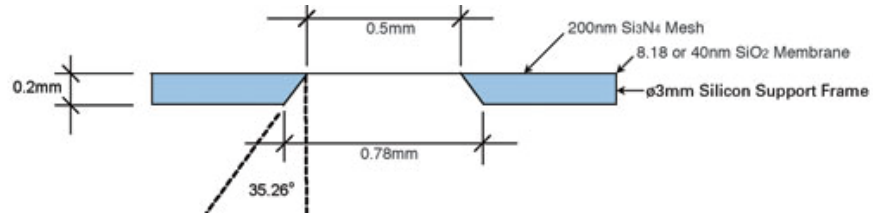


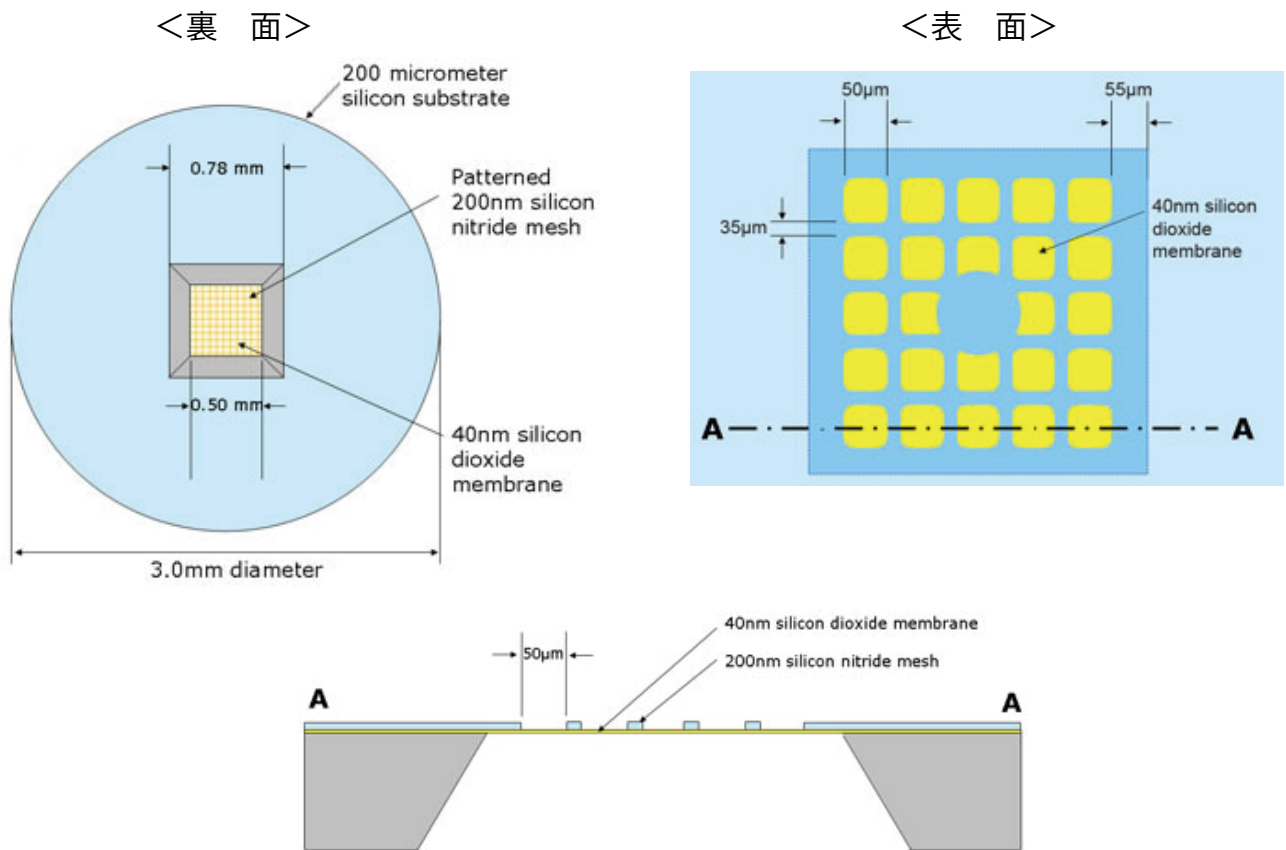
Silicon Dioxide Support Film

Silicon Dioxide Support Film は特許を取得した最新技術の半導体と MEMS 製造法により製造されます。

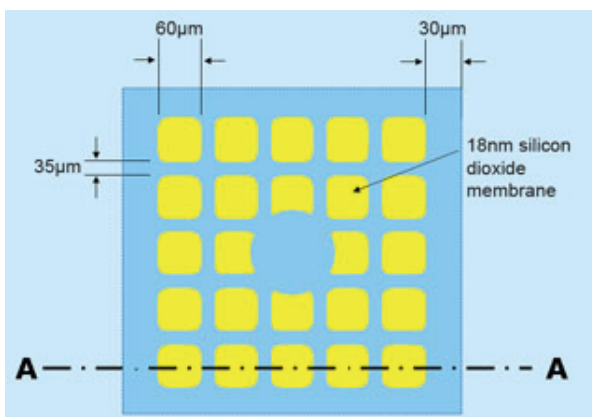
● サイズ及び形



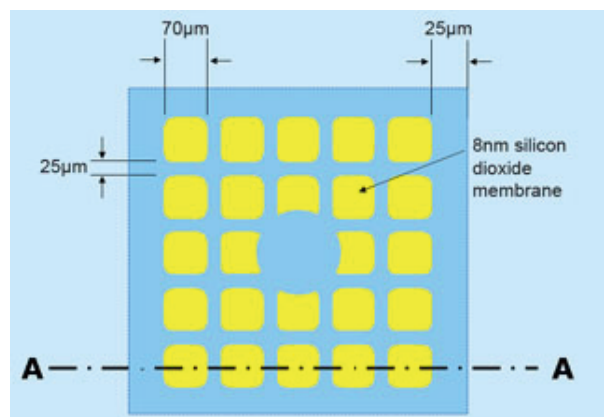
● 40nm Membrane Thickness



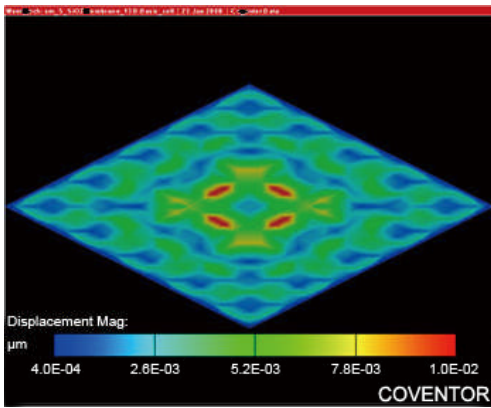
● 18nm Membrane Thickness



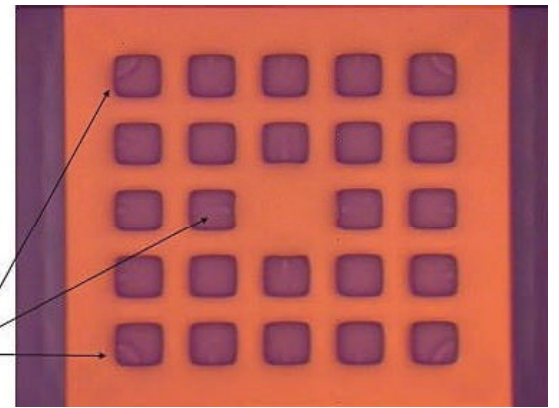
● 8nm Membrane Thickness



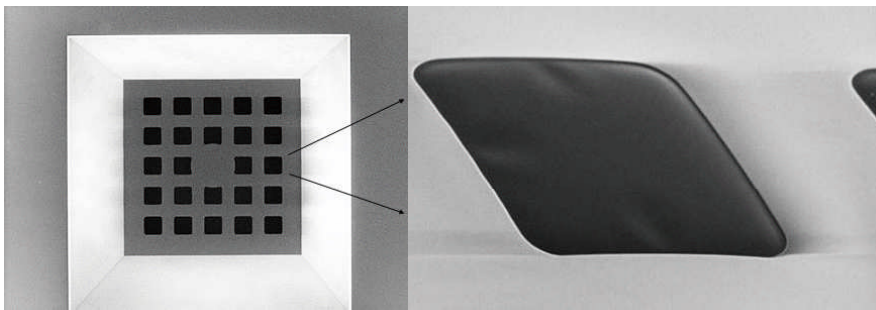
Silicon Dioxide (SiO₂) Support Film



SiO₂ 膜の平坦性シミュレーション
(0.5 × 0.5mm window)



極僅かな歪み
(光学イメージ)



傾き 60° から見た Silicon Dioxide Support Film 50 × 50um
平坦性が見て取れます